

**Amendments to the Specification:**

This listing of amended paragraphs of the specification will replace all prior versions of the corresponding paragraphs of the specification in the application.

**Listing of Amended Paragraphs of the Specification:**

Please amend the paragraph beginning on page 1, line 27 to read as follows:

Conventional technology includes a method for deuteration of an aromatic compound under high temperature condition using heavy water and hydrochloric acid (Can. J. Chem. 1974, [[52]]52, 2169, etc.), a method for deuteration of an aromatic compound under basic condition using supercritical ~~water~~ $D_2O$  (Tetrahedron Letters 1996, [[37]]37, 3445, etc.), a method for deuteration of an aromatic compound having a hydrophilic group under basic condition using a catalyst (JP-A-62-56441, etc.), a method for deuteration of an aromatic compound at high temperature using a non-activated catalyst (JP-A-63-198638, etc.), a method for deuteration of an organic compound under basic condition using heavy hydrogen peroxide (U.S. Pat. No. 3,849,458, etc.), a method for deuteration of a halogen atom once introduced to an aromatic compound (JP-A-6-228014, etc.), etc.

Please amend the paragraph beginning on page 2, line 21 to read as follows:

Further, a method for deuteration under high temperature condition is difficult to be applied to a compound labile to decomposition at high temperature and a method for using supercritical ~~water~~ $D_2O$  has a problem that a compound to be a reaction substrate tends to be decomposed due to significantly high reactivity of supercritical ~~water~~ $D_2O$ .